

Hiroshi Amano

List of Publications by Year in descending order

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208
papers

11,809
citations

87888
38
h-index

27406
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all docs

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docs citations

208
times ranked

5527
citing authors

#	ARTICLE	IF	CITATIONS
1	Ohmic Contact to $\langle 10\bar{1}\rangle$ -Type GaN Enabled by Post-Growth Diffusion of Magnesium. <i>IEEE Electron Device Letters</i> , 2022, 43, 150-153.	3.9	12
2	Inhomogeneous Barrier Height Characteristics of n-Type AlInP for Red AlGaNp-Based Light-Emitting Diodes. <i>ECS Journal of Solid State Science and Technology</i> , 2022, 11, 035007.	1.8	0
3	Sputtered polycrystalline MgZnO/Al reflective electrodes for enhanced light emission in AlGaN-based homojunction tunnel junction DUV-LED. <i>Applied Physics Express</i> , 2022, 15, 044001.	2.4	7
4	Improved performance of deep ultraviolet AlGaN-based light-emitting diode by reducing contact resistance of Al-based reflector. <i>Journal of Alloys and Compounds</i> , 2022, 910, 164895.	5.5	2
5	Space-Charge Profiles and Carrier Transport Properties in Dopant-Free GaN-Based p-n Junction Formed by Distributed Polarization Doping. <i>Physica Status Solidi - Rapid Research Letters</i> , 2022, 16, .	2.4	4
6	Impact of heat treatment process on threshold current density in AlGaN-based deep-ultraviolet laser diodes on AlN substrate. <i>Applied Physics Express</i> , 2021, 14, 051003.	2.4	9
7	Optimization of Ni/Ag-Based Reflectors to Improve the Performance of 273 nm Deep Ultraviolet AlGaN-Based Light Emitting Diodes. <i>ECS Journal of Solid State Science and Technology</i> , 2021, 10, 045005.	1.8	3
8	Electrical properties and structural defects of p-type GaN layers grown by halide vapor phase epitaxy. <i>Journal of Crystal Growth</i> , 2021, 566-567, 126173.	1.5	9
9	Demonstration of Observation of Dislocations in GaN by Novel Birefringence Method. <i>Physica Status Solidi (B): Basic Research</i> , 2020, 257, 1900553.	1.5	5
10	Suppression of Green Luminescence of Mg-ion-Implanted GaN by Subsequent Implantation of Fluorine Ions at High Temperature. <i>Physica Status Solidi (B): Basic Research</i> , 2020, 257, 1900554.	1.5	12
11	Indium incorporation and optical properties of polar, semipolar and nonpolar InAlN. <i>Semiconductor Science and Technology</i> , 2020, 35, 035004.	2.0	11
12	Improvement of The Light Output of Blue InGaN-Based Light Emitting Diodes by Using a Buried Stripe-Typen-Contact and Reflective Bonding Pad. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 015021.	1.8	0
13	The 2020 UV emitter roadmap. <i>Journal Physics D: Applied Physics</i> , 2020, 53, 503001.	2.8	289
14	Surface passivation of light emitting diodes: From nano-size to conventional mesa-etched devices. <i>Surfaces and Interfaces</i> , 2020, 21, 100765.	3.0	11
15	Epitaxial Combination of Two-Dimensional Hexagonal Boron Nitride with Single-Crystalline Diamond Substrate. <i>ACS Applied Materials & Interfaces</i> , 2020, 12, 46466-46475.	8.0	13
16	Electrical properties of GaN metal-insulator-semiconductor field-effect transistors with Al ₂ O ₃ /GaN interfaces formed on vicinal Ga-polar and nonpolar surfaces. <i>Applied Physics Letters</i> , 2020, 117, .	3.3	12
17	Improved Leakage and Output Characteristics of Pixelated LED Array for Headlight application. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 045011.	1.8	1
18	Improving the Leakage Characteristics and Efficiency of GaN-based Micro-Light-Emitting Diode with Optimized Passivation. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 055001.	1.8	35

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19	Halide vapor phase epitaxy of p-type Mg-doped GaN utilizing MgO. <i>Applied Physics Express</i> , 2020, 13, 061007.	2.4	12
20	Pulsed-flow growth of polar, semipolar and nonpolar AlGaN. <i>Journal of Materials Chemistry C</i> , 2020, 8, 8668-8675.	5.5	9
21	Effects of Ultraviolet Wavelength and Ambient Temperature on Reliability of Silicones in InAlGaN-Based Light-Emitting-Diode Package. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 035005.	1.8	2
22	Oblique-Angle Deposited SiO ₂ /Al Omnidirectional Reflector for Enhancing the Performance of AlGaN-Based Ultraviolet Light-Emitting Diode. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 026005.	1.8	5
23	Using SiO ₂ -Based Distributed Bragg Reflector to Improve the Performance of AlGaNP-Based Red Micro-Light Emitting Diode. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 036002.	1.8	4
24	Demonstration of Observation of Dislocations in GaN by Novel Birefringence Method. <i>Physica Status Solidi (B): Basic Research</i> , 2020, 257, 2070021.	1.5	0
25	Experimental observation of high intrinsic thermal conductivity of AlN. <i>Physical Review Materials</i> , 2020, 4, .	2.4	60
26	Heavy Mg Doping to Form Reliable Rh Reflective Ohmic Contact for 278 nm Deep Ultraviolet AlGaN-Based Light-Emitting Diodes. <i>ECS Journal of Solid State Science and Technology</i> , 2020, 9, 065016.	1.8	6
27	Thermodynamic analysis of the gas phase reaction of Mg-doped GaN growth by HVPE using MgO. <i>Japanese Journal of Applied Physics</i> , 2020, 59, 088001.	1.5	5
28	Growth of high-quality GaN by halogen-free vapor phase epitaxy. <i>Applied Physics Express</i> , 2020, 13, 085509.	2.4	6
29	Fabrication of a GaInN/GaInP/GaInAs/Ge four-junction solar cell using the wafer bonding technology. <i>Japanese Journal of Applied Physics</i> , 2019, 58, 072003.	1.5	0
30	A 271.8 nm deep-ultraviolet laser diode for room temperature operation. <i>Applied Physics Express</i> , 2019, 12, 124003.	2.4	217
31	Hole injection mechanism in the quantum wells of blue light emitting diode with V pits for micro-display application. <i>Applied Physics Express</i> , 2019, 12, 102016.	2.4	6
32	Untwinned semipolar (101...3) Al _x GaN layers grown on m-plane sapphire. <i>Semiconductor Science and Technology</i> , 2019, 34, 125012.	2.0	4
33	Via-Hole-Type Flip-Chip Packaging to Improve the Thermal Characteristics and Reliability of Blue Light Emitting Diodes. <i>ECS Journal of Solid State Science and Technology</i> , 2019, 8, Q165-Q170.	1.8	5
34	The emergence and prospects of deep-ultraviolet light-emitting diode technologies. <i>Nature Photonics</i> , 2019, 13, 233-244.	31.4	800
35	Fully Ion Implanted Normally-Off GaN DMOSFETs with ALD-Al ₂ O ₃ Gate Dielectrics. <i>Materials</i> , 2019, 12, 689.	2.9	21
36	Nonpolar m-plane layers grown on m-plane sapphire by MOVPE. <i>Journal of Crystal Growth</i> , 2019, 512, 100-104.	15.5	15

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37	Aluminium incorporation in polar, semi- and non-polar AlGaN layers: a comparative study of x-ray diffraction and optical properties. <i>Scientific Reports</i> , 2019, 9, 15802.	3.3	12
38	Electronic structure analysis of core structures of threading dislocations in GaN. , 2019, , .		1
39	Reduction of Dislocations in GaN on Silicon Substrate Using In Situ Etching. <i>Physica Status Solidi (B): Basic Research</i> , 2018, 255, 1700387.	1.5	6
40	$\langle 10\bar{1}0 \rangle$ Plane GaN Schottky Barrier Diodes Fabricated With MOVPE Layer on Several Off-Angle $\langle 10\bar{1}0 \rangle$ Plane GaN Substrates. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2018, 215, 1700645.	1.8	20
41	Full-duplex light communication with a monolithic multicomponent system. <i>Light: Science and Applications</i> , 2018, 7, 83.	16.6	59
42	MOVPE growth and high-temperature annealing of (101̄0) AlN layers on (101̄0) sapphire. <i>Journal of Crystal Growth</i> , 2018, 502, 14-18.	1.5	14
43	Reduction of Dislocations in GaN on Silicon Substrate Using In Situ Etching (Phys. Status Solidi B) Tj ETQq1 1 0.784314 rgBT ₁ /Overlock High-temperature thermal annealing of nonpolar (100) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 487 Td (xmlns:mml="http://www.w3.org/1998/Math/MathML")		
44			

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55	Improved crystal quality of semipolar (101-3) GaN on Si(001) substrates using AlN/GaN superlattice interlayer. <i>Journal of Crystal Growth</i> , 2016, 454, 114-120.	1.5	15
56	Deep level study of Mg-doped GaN using deep level transient spectroscopy and minority carrier transient spectroscopy. <i>Physical Review B</i> , 2016, 94, .	3.2	12
57	Emission Characteristics of InGaN/GaN Core-Shell Nanorods Embedded in a 3D Light-Emitting Diode. <i>Nanoscale Research Letters</i> , 2016, 11, 215.	5.7	35
58	Effect of piezoelectric field on carrier dynamics in InGaN-based solar cells. <i>Journal Physics D: Applied Physics</i> , 2016, 49, 025103.	2.8	19
59	Highly elongated vertical GaN nanorod arrays on Si substrates with an AlN seed layer by pulsed-mode metal-organic vapor deposition. <i>CrystEngComm</i> , 2016, 18, 1505-1514.	2.6	33
60	Growth of GaN on sapphire via low-temperature deposited buffer layer and realization of p-type GaN by Mg doping followed by low-energy electron beam irradiation (Nobel Lecture). <i>Annalen Der Physik</i> , 2015, 527, 327-333.	2.4	16
61	Bildung von GaN-Schichten auf Saphir durch Niedertemperatur-Pufferschichten und Erzeugung von p-GaN durch Magnesium-Dotierung und Elektronenbeschuss (Nobel-Aufsatz). <i>Angewandte Chemie</i> , 2015, 127, 7874-7879.	2.0	1
62	Growth of GaN Layers on Sapphire by Low-Temperature Deposited Buffer Layers and Realization of p-type GaN by Magesium Doping and Electron Beam Irradiation (Nobel Lecture). <i>Angewandte Chemie - International Edition</i> , 2015, 54, 7764-7769.	13.8	37
63	Polarization dilution in a Ga-polar UV-LED to reduce the influence of polarization charges. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2015, 212, 920-924.	1.8	5
64	Electrical characteristics of <i>a</i> -plane low-Mg-doped p-GaN Schottky contacts. <i>Physica Status Solidi (B): Basic Research</i> , 2015, 252, 1024-1030.	1.5	3
65	Nobel Lecture: Growth of GaN on sapphire via low-temperature deposited buffer layer and realization of p -type GaN by Mg doping followed by low-energy electron beam irradiation. <i>Reviews of Modern Physics</i> , 2015, 87, 1133-1138.	45.6	90
66	Growth of GaN on Sapphire via Low-Temperature Deposited Buffer Layer and Realization of p-Type GaN by Mg Doping Followed by Low-Energy Electron Beam Irradiation. <i>International Journal of Modern Physics B</i> , 2015, 29, 1530015.	2.0	2
67	Excitation density dependence of radiative and nonradiative recombination lifetimes in InGaN/GaN multiple quantum wells. <i>Physica Status Solidi (B): Basic Research</i> , 2015, 252, 940-945.	1.5	16
68	Optically pumped lasing properties of \$(1\text{ar}{\{1\}}01)\$ InGaN/GaN stripe multiquantum wells with ridge cavity structure on patterned (001) Si substrates. <i>Applied Physics Express</i> , 2015, 8, 022702.	2.4	28
69	Dynamic properties of excitons in ZnO/AlGaN/GaN hybrid nanostructures. <i>Scientific Reports</i> , 2015, 5, 7889.	3.3	6
70	Highly ordered catalyst-free InGaN/GaN core-shell architecture arrays with expanded active area region. <i>Nano Energy</i> , 2015, 11, 294-303.	16.0	47
71	MOCVD of Nitrides. , 2015, , 683-704.	4	
72	Growth of InGaN/GaN multiple quantum wells on size-controllable nanopryamid arrays. <i>Japanese Journal of Applied Physics</i> , 2014, 53, 030306.	1.5	7

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73	In situX-ray investigation of changing barrier growth temperatures on InGaN single quantum wells in metal-organic vapor phase epitaxy. <i>Journal of Applied Physics</i> , 2014, 115, 094906.	2.5	9
74	Morphology development of GaN nanowires using a pulsed-mode MOCVD growth technique. <i>CrystEngComm</i> , 2014, 16, 2273-2282.	2.6	82
75	Multijunction GaInN-based solar cells using a tunnel junction. <i>Applied Physics Express</i> , 2014, 7, 034104.	2.4	22
76	Enhancement of light output power on GaN-based light-emitting diodes using two-direction stripe-patterned sapphire substrate. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2014, 11, 722-725.	0.8	4
77	Improvement of light extraction efficiency of 350nm emission UV light-emitting diodes. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2014, 11, 836-839.	0.8	5
78	X-ray investigations of GaInN single quantum wells grown by atomic layer epitaxy and metalorganic vapor phase epitaxy. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2014, 11, 393-396.	0.8	0
79	Introduction Part A. Progress and Prospect of Growth of Wide-Band-Gap III-Nitrides. <i>Topics in Applied Physics</i> , 2013, , 1-9.	0.8	0
80	Effects of exciton localization on internal quantum efficiency of InGaN nanowires. <i>Journal of Applied Physics</i> , 2013, 114, .	2.5	38
81	Characteristics of a-plane GaN films grown on optimized silicon-dioxide-patterned r-plane sapphire substrates. <i>Thin Solid Films</i> , 2013, 546, 108-113.	1.8	7
82	Structural evolution of AlN buffer and crystal quality of GaN films on a- and c-sapphire grown by metalorganic vapor phase epitaxy. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2013, 10, 369-372.	0.8	5
83	Effects of Nano- and Microscale SiO ₂ Masks on the Growth of a-Plane GaN Layers on r-Plane Sapphire. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JC04.	1.5	1
84	Thick InGaN Growth by Metal Organic Vapor Phase Epitaxy with Sputtered InGaN Buffer Layer. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JB11.	1.5	12
85	Combination of Indium-Tin Oxide and SiO ₂ /AlN Dielectric Multilayer Reflective Electrodes for Ultraviolet-Light-Emitting Diodes. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JG07.	1.5	11
86	Microstructure Analysis of AlGaN on AlN Underlying Layers with Different Threading Dislocation Densities. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JE22.	1.5	3
87	Analysis of Broken Symmetry in Convergent-Beam Electron Diffraction along <112̄0> and <11̄00> Zone-Axes of AlN for Polarity Determination. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JE15.	1.5	5
88	Dislocation density dependence of stimulated emission characteristics in AlGaN/Al multiquantum wells. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2013, 10, 1537-1540.	0.8	6
89	K16200 Future Prospect of Nitride Semiconductor Devices. <i>The Proceedings of Mechanical Engineering Congress Japan</i> , 2013, 2013, _K16200-1_-K16200-3_.	0.0	0
90	Thermoelectric Power Measurement of Catalyst-free Si-doped GaAs Nanowires. <i>Materials Research Society Symposia Proceedings</i> , 2012, 1439, 83-87.	0.1	1

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91	MOVPE growth of nonpolar α -plane GaN with low oxygen contamination and specular surface on a freestanding GaN substrate. <i>Journal of Crystal Growth</i> , 2012, 351, 126-130.	1.5	0
92	Laser lift-off of AlN/sapphire for UV light-emitting diodes. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2012, 9, 753-756.	0.8	34
93	Fabrication of AlInN/AlN/GaN/GaN heterostructure field-effect transistors. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2012, 9, 942-944.	0.8	1
94	Growth of GaN and AlGaN on (100) Ga_2O_3 substrates. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2012, 9, 519-522.	0.8	30
95	Properties of nitride-based photovoltaic cells under concentrated light illumination. <i>Physica Status Solidi - Rapid Research Letters</i> , 2012, 6, 145-147.	2.4	12
96	Demonstration of diamond field effect transistors by AlN/diamond heterostructure. <i>Physica Status Solidi - Rapid Research Letters</i> , 2011, 5, 125-127.	2.4	39
97	Growth of AlGaN/GaN heterostructure on vicinal $\langle 1\bar{1}0 \rangle$ plane free-standing GaN substrates prepared by the Na flux method. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1191-1194.	1.8	4
98	Low leakage current in AlGaN/GaN HFETs with preflow of Mg source before growth of u-GaN buffer layer. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1607-1610.	1.8	2
99	Development of high efficiency 255-355 nm AlGaN-based light-emitting diodes. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1594-1596.	1.8	98
100	AlGaN/GaN heterostructure field-effect transistor. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1614-1616.	1.8	13
101	Frontispiece: Development of high efficiency 255-355 nm AlGaN-based light-emitting diodes (Phys. Status Solidi) $T_j = 10.7$ K, $E_T = 0.784$ eV	1.8	10
102	Internal quantum efficiency and internal loss of ultraviolet laser diodes on the low dislocation density AlGaN underlying layer. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 464-466.	0.8	4
103	Achieving high-growth-rate in GaN homoepitaxy using high-density nitrogen radical source. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 2089-2091.	0.8	12
104	Injection efficiency in AlGaN-based UV laser diodes. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 2384-2386.	0.8	14
105	Drain bias stress and memory effects in AlGaN/GaN heterostructure field-effect transistors with p-GaN gate. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 2424-2426.	0.8	0
106	Reduction in threshold current density of 355 nm UV laser diodes. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 1564-1568.	0.8	13
107	Evidence for moving of threading dislocations during the VPE growth in GaN thin layers. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 1487-1490.	0.8	5
108	Optimization of initial MOVPE growth of non-polar α -and β -plane GaN on Na flux grown LPE-GaN substrates. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 2095-2097.	0.8	3

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109	Transparent electrode for UV light-emitting-diodes. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 2375-2377.	0.8	7
110	Fabrication of Nonpolar a -Plane Nitride-Based Solar Cell on r -Plane Sapphire Substrate. <i>Applied Physics Express</i> , 2011, 4, 101001.	2.4	12
111	Internal Quantum Efficiency of Whole-Composition-Range AlGaN Multiquantum Wells. <i>Applied Physics Express</i> , 2011, 4, 052101.	2.4	220
112	Freestanding Highly Crystalline Single Crystal AlN Substrates Grown by a Novel Closed Sublimation Method. <i>Applied Physics Express</i> , 2011, 4, 045503.	2.4	6
113	Improvement of Light Extraction Efficiency for AlGaN-Based Deep Ultraviolet Light-Emitting Diodes. <i>Japanese Journal of Applied Physics</i> , 2011, 50, 122101.	1.5	27
114	Compensation effect of Mg-doped a - and c -plane GaN films grown by metalorganic vapor phase epitaxy. <i>Journal of Crystal Growth</i> , 2010, 312, 3131-3135.	1.5	30
115	Defects in highly Mg-doped AlN. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2010, 207, 1299-1301.	1.8	1
116	Improved Efficiency of 255-280 nm AlGaN-Based Light-Emitting Diodes. <i>Applied Physics Express</i> , 2010, 3, 061004.	2.4	233
117	Activation of Mg-Doped p-Type Al _{0.17} Ga _{0.83} N in Oxygen Ambient. <i>Japanese Journal of Applied Physics</i> , 2009, 48, 101002.	1.5	1
118	Strong Emission from GaInN/GaN Multiple Quantum Wells on High-Crystalline-Quality Thick m -Plane GaN Underlying Layer on Grooved GaN. <i>Applied Physics Express</i> , 2009, 2, 061004.	2.4	11
119	High-performance UV emitter grown on high-crystalline-quality AlGaN underlying layer. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2009, 206, 1199-1204.	1.8	41
120	Activation energy of Mg in a -plane Ga _{1-x} In _x N ($0 < x < 1$) N (0 < Tj < 100 K). <i>Journal of Crystal Growth</i> , 2009, 311, 2887-2890.	1.5	1
121	One-sidewall-seeded epitaxial lateral overgrowth of a -plane GaN by metalorganic vapor-phase epitaxy. <i>Journal of Crystal Growth</i> , 2009, 311, 2887-2890.	1.5	31
122	InGaN growth with various InN mole fractions on m -plane ZnO substrate by metalorganic vapor phase epitaxy. <i>Journal of Crystal Growth</i> , 2009, 311, 2929-2932.	1.5	2
123	Growth of thick GaInN on grooved (101̄1̄) GaN/(101̄2̄) 4H-SiC. <i>Journal of Crystal Growth</i> , 2009, 311, 2926-2928.	1.5	3
124	Temperature dependence of excitonic transitions in a -plane AlN epitaxial layers. <i>Journal of Applied Physics</i> , 2009, 105, 083533.	2.5	17
125	Dynamical study of the radiative recombination processes in GaN/AlGaN QWs. <i>Journal of Materials Science: Materials in Electronics</i> , 2008, 19, 316-318.	2.2	0
126	Sidewall epitaxial lateral overgrowth of nonpolar a -plane GaN by metalorganic vapor phase epitaxy. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2008, 5, 1575-1578.	0.8	16

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127	Improvement in crystalline quality of thick GaInN on m-plane 6H-SiC substrates using sidewall epitaxial lateral overgrowth. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2008, 5, 3045-3047.	0.8	2
128	Realization of low-dislocation-density, smooth surface, and thick GaInN films on m-plane GaN templates. <i>Journal of Crystal Growth</i> , 2008, 310, 3308-3312.	1.5	15
129	Control of p-type conduction in a-plane $\text{Ga}_{1-x}\text{In}_x\text{N}$ ($0 < x < 0.10$) grown on r-plane sapphire substrate by metalorganic vapor-phase epitaxy. <i>Journal of Crystal Growth</i> , 2008, 310, 4996-4998.	1.5	1
130	Control of stress and crystalline quality in GaInN films used for green emitters. <i>Journal of Crystal Growth</i> , 2008, 310, 4920-4922.	1.5	8
131	AlN and AlGaN by MOVPE for UV Light Emitting Devices. <i>Materials Science Forum</i> , 2008, 590, 175-210.	0.3	2
132	High hole concentration in Mg-doped a-plane $\text{Ga}_{1-x}\text{In}_x\text{N}$ ($x < 0.30$) grown on r-plane sapphire substrate by metalorganic vapor phase epitaxy. <i>Applied Physics Letters</i> , 2008, 93, .	3.3	14
133	Photoluminescence from highly excited AlN epitaxial layers. <i>Applied Physics Letters</i> , 2008, 92, .	3.3	31
134	Realization of High-Crystalline-Quality Thick m-Plane GaInN Film on 6H-SiC Substrate by Epitaxial Lateral Overgrowth. <i>Japanese Journal of Applied Physics</i> , 2007, 46, L948.	1.5	14
135	Photonic Devices. , 2007, , 97-230.		1
136	Fundamental Properties of Wide Bandgap Semiconductors. , 2007, , 25-96.		0
137	Crystallographic polarity and crystallinity characterization of polar and nonpolar GaN epitaxial films by X-ray diffraction analyses. <i>Physica Status Solidi (B): Basic Research</i> , 2007, 244, 1775-1779.	1.5	2
138	Preface to Special Issue on Market Explosion of 405 nm Emission Semiconductor Laser of GaN System. <i>The Review of Laser Engineering</i> , 2007, 35, 64-64.	0.0	0
139	Electroluminescent Diodes and Laser Diodes. , 2006, , 529-546.		0
140	Effects of Si doping position on the emission energy and recombination dynamics of GaN/AlGaN multiple quantum wells. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2006, 203, 149-153.	1.8	1
141	X-ray diffraction reciprocal lattice space mapping of a-plane AlGaN on GaN. <i>Physica Status Solidi (B): Basic Research</i> , 2006, 243, 1524-1528.	1.5	12
142	Origin of defect-insensitive emission probability in In-containing (Al,In,Ga)N alloy semiconductors. <i>Nature Materials</i> , 2006, 5, 810-816.	27.5	625
143	Details of the improvement of crystalline quality of a-plane GaN using one-step lateral growth. <i>Materials Research Society Symposia Proceedings</i> , 2006, 955, 1.	0.1	0
144	Optical Properties of Undoped, n-Doped and p-Doped GaN/AlN Superlattices. <i>Materials Research Society Symposia Proceedings</i> , 2006, 955, 1.	0.1	1

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145	Fabrication of high-performance photodetector based on AlGaN/GaN hetero-field-effect transistors with p-GaN gate. Materials Research Society Symposia Proceedings, 2006, 955, 1.	0.1	0
146	The Evolution of Nitride Semiconductors. , 2005, , 23-38.		2
147	Characterization of a-plane AlGaN/GaN heterostructure grown on r-plane sapphire substrate. Materials Research Society Symposia Proceedings, 2005, 892, 121.	0.1	0
148	Highly p-Type a-GaN Grown on r-Plane Sapphire Substrate. Materials Research Society Symposia Proceedings, 2005, 892, 381.	0.1	0
149	High-Power Operation of Pure Blue GaN-Based Semiconductor Laser. The Review of Laser Engineering, 2005, 33, 651-654.	0.0	0
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